

IN THE CLAIMS:

Please cancel Claims 1 - 5 without prejudice.

1 - 12. (Cancelled)

13. (Previously Presented) A processing chamber component resistant to a plasma including fluorine and oxygen species, said component comprising:

a high purity aluminum substrate where particulates formed from mobile impurities have a particle size distribution such that no more than 0.2 % of the particles are larger than 20 μm , with no particles being larger than 50 μm ;

an anodized coating on a surface of the high purity aluminum substrate; and

a protective coating comprising yttrium oxide overlying the anodized coating.

14. (Previously Presented) A processing chamber component in accordance with claim 13, wherein said high purity aluminum substrate particle size distribution with respect to particulates formed from mobile impurities is such that at least 95 % of all particles must be less than 5 μm in size, with no more than 0.1 % of the particles being larger than 20 μm , and with no particles being larger than 40 μm .

15. (Previously Presented) A processing chamber component in accordance with claim 13, wherein said protective coating includes aluminum oxide up to about 10 % by weight.

16. (Previously Presented) A process chamber component in accordance with claim 13, wherein said protective coating is 99.95 % by weight or greater yttrium oxide.

17. (Previously Presented) A process chamber component in accordance with claim 13, wherein said protective coating is coating applied using a method selected from the group consisting of spray coating, chemical vapor deposition, and physical vapor deposition.

18. (Previously Presented) A process chamber component in accordance with claim 17, where the coating comprising yttrium oxide has been mechanically finished to remove loose particles.